Tem perature induced transitions between insulator, m etal, and quantum H all states

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A bstract

We report the observation of temperature induced transitions between insulator, metal, and quantum Hall behaviors for transport coecients in the very dilute high mobility two-dimensional electron system in silicon at a magnetic eld corresponding to Landau level lling factor = 1.0 ur data show that as the temperature decreases, the extended states at = 1 (above the Fermilevel at higher temperature so that the system is insulating) sink below the Fermilenergy, so that the quantum Halle ect occurs. As the extended states cross the Fermilevel, the conductivity has a temperature dependence characteristic of a metallic system.

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In the study of two dimensional electron systems (2DES), there have been considerable interest in transitions between insulating and quantum Hall (QH) states. Thus far such transitions have only been observed as the magnetic eld and/or the electron density are changed. However, in this paper we present experimental evidence that transitions between insulator, metal, and QH-like behaviors for transport coecients can also be observed at xed eld and carrier density as the temperature is decreased. In particular, we have observed 2DES delocalization (insulator to metal transition) with decreasing temperature, whereas increasing localization is the usual consequence of lowering the temperature for a 2DES.

It was reported recently both for high-mobility silicon inversion layers [1] and for lowm obility G aAs/(Al,Ga)As heterostructures [2,3] that 2DES, strongly localized in zero magnetic eld (B = 0), can nevertheless manifest the integer Q H e ect. References [4{6] discuss this magnetic-eld-induced transition from a many-body point of view, whereas Refs. [2,3] ignore the e ects of electron-electron interactions and consider the arguments of K hm elnitskii [7] and Laughlin [8] along with the global phase diagram proposed by Kivelson, Lee, and Zhang [9] as the basis for the insulator-QH transition. According to Refs. [7,8], extended states, which lie above the Fermi energy (E_F) at B=0 (i.e. making the system insulating) decrease in energy as B is increased [see in set in Fig. 1 (a)] and may sink below E_F [10]. At zero tem perature, the diagonal conductivity ($_{xx}$) is zero except when extended states are at E_F . As long as E_F lies below the lowest extended state, the Hall conductivity ($_{\rm xy}$) is also zero and the system is insulating. For each band of extended states below $E_{\,\mathrm{F}}$, $_{\,\mathrm{xy}}$ increases by e²=h, providing the next integer Q H state. In high magnetic elds, the extended states approximately follow half-led Landau levels with lling factors = n_s =(eB =ch) = 1=2, 3/2, 5/2 etc (here n_s is the electron density, e is the electron charge, c is the speed of light, and h is the Plank constant). If temperature is not zero, xx usually displays activated behavior except when there are extended states at E_F with the activation energy equal to the energy di erence between $E_{\,\mathrm{F}}\,$ and the nearest extended state.

Magnetic-eld-induced transitions between insulating and QH groundstates have also been investigated in very dilute high-mobility GaAs/(Al,Ga)As heterostructures in the ex-

trem e quantum \lim it (see, e.g., Ref. [12] and references therein) and in Si inversion layers around = 1, 2, and 6 (Ref. [5,6]). In some papers [4{6,13{15}}] the fact that the insulating state can be disrupted by integer or fractional QH resistivity m in in a was discussed in terms of the formation of a pinned electron solid melting at integer or fractional. However, the global phase diagram [9] can also explain magnetic—eld-induced transitions between QH (at = 1, 1/3, or 1/5) and insulating ground states without invoking collective elects; though, recently observed direct transitions from = 2=7 and 2/5 (Refs. [15,16]) and = 6 (Ref. [6]) to insulating states are contradictions of the global phase diagram. At very low n_s , the QH elect breaks down even at integer or fractional [1,15]; nevertheless x_x still has minimal at these lling factors.

Here we consider the = 1 integer QH e ect at the border of it's existence, at very low n_s . There is de nitely no electron solid for these conditions. We report experimental evidence for transitions from insulating to metallic and QH types of behavior of transport coe cients at constant lling factor = 1 as the temperature is varied. We will de ne a system as insulating if its conductivities exhibit insulator-like temperature behavior, i.e., $d_{xx}=dT$, $d_{xy}=dT>0$ with $d_{xy}< d_{xx}< d_{xy}=dT$. Similarly we do no metallic behavior as $d_{xx}=dT$, $d_{xy}=dT<0$. Finally, a QH state is characterized by $d_{xy}=dT>0$ as the temperature is lowered. The observed transitions from insulating behavior can be explained by assuming that at $d_{xy}=dT>0$ the lowest band of extended states, which lies above the Fermi energy at high temperature as expected for an insulator, drops as the temperature is lowered. The system behaves as a metal as it passes through the Fermi level, and nally displays the QH extended after the band of extended states sinks below $d_{xy}=dT>0$.

Two samples from wafers with dierent mobilities have been studied: Si-14, which has a maximum mobility ($_{max}$) of 1:9 $_{max}$ 10 cm $_{max}$ 7/V s, and Si-22, which has $_{max}$ = 3:5 $_{max}$ 10 cm $_{max}$ 7/V s. The samples are rectangular with a source to drain length of 5 mm, a width of 0.8 mm, and an intercontact distance of 1.25 mm. Resistances were measured using a four-term in allow-frequency (typically 8 Hz) AC technique using cold ampliers with input resistances $_{max}$ 10 installed inside the cryostat. The output of these ampliers was connected to a

standard lock—in amplier. Great care was taken to ensure that all data discussed here were obtained where the I V characteristics are linear.

The dependencies of $_{xx}$ and $_{xy}$ (both are in units of h=e²) on magnetic eld for three di erent temperatures are shown in Fig. 1 (a). At the highest temperature, $_{xx}$ (B) is at up to B 4 T and lies well above h=e². As the temperature decreases, miniman near integer lling factors = 1 and 2 and maxima at intermediate lling factors 1:5 and 2.7 appear. The Hall resistance is almost T-independent; at low temperature, narrow QH plateaux start to develop near = 1 and 2 [17]. Note that as the temperature is decreased from 1.82 K to 942 mK, $_{xx}$ at = 1 decreases while remaining larger than $_{xy}$ = h=e²; this corresponds to d $_{xx}$ =dT < 0 characteristic of a metallic state and rejects delocalization with decreasing temperature, whereas $_{xx}$ increases at B = 0, indicating an insulating groundstate. At still lower temperature, $_{xx}$ at = 1 sinks below $_{xy}$ = h=e² penetrating into the QH region.

Before proceeding further, we must demonstrate that the observed metallic-like decrease in xx near = 1 is a fundamentale ect of the whole 2DES and not an artifact of special current paths such as, e.g., edge currents [18]. Furtherm ore, in principle the current distribution in a 2DES at low temperatures can be inhomogeneous. If this is the case, it is di cult to draw conclusions about the behavior of xx using xx data. To check these points and to obtain information about xx directly, we have measured the impedance between the 2D channel and the metallic gate using an RC bridge. The real part of the bridge imbalance signal is proportional to inverse x averaged over the sample area. The magnetic eld dependence of the signal proportional to $\frac{1}{xx}$ is shown in Fig. 1 (b). One can see that it is qualitatively \sin ilar to $_{xx}$ (B) as expected for the case of $_{xx}$ > $_{xy}$. For \normal", high-n_s QH e ect, where $_{xx}$ < $_{xy}$, the dependence is qualitatively dierent: at integer lling factors = 1 and 2, $\frac{1}{xx}$ has extrem e m axim a instead of m in in a, see Fig. 1 (b) in set]. A gain, as the tem perature is lowered, xx increases at x = 1, showing m etallic behavior, and decreases at and $\frac{1}{xx}$ (B) shows that the current distribution can be considered homogeneous and that we can therefore calculate $_{xx}$ and $_{xy}$ from the data for $_{xx}$ and $_{xy}$.

Figure 2 shows the tem perature dependence of $_{xx}$ at = 1 for four dierent electron densities. For the lowest n_s , $_{xx}$ (T) always lies above $h=e^2$ and monotonically increases as the tem perature is decreased showing an activated tem perature behavior (see inset). On the other hand, for the highest electron density, $_{xx}$ always lies below $h=e^2$ and monotonically decreases as the tem perature is decreased below T=3 K showing QH type of behavior. But for the two middle n_s , $_{xx}$ (T) are nonmonotonic, increasing exponentially at high temperatures (see inset) and decreasing at lower ones. This nonmonotonic behavior implies, as shown below, temperature induced transitions from insulator-like to metallic and QH types of behavior.

The tem perature dependencies of $_{xx}$ and $_{xy}$, computed from the data for $_{xx}$ and $_{xy}$, are shown in Fig. 3. Figure 3 (a) shows tem perature behavior of $_{xx}$ and $_{xy}$ for the case of \ordinary", \high-n_s" QH e ect. Diagonal conductivity, which is always less than e^2 =2h, monotonically decreases, and $_{xy}$, which is always higher than e^2 =2h, monotonically increases as the tem perature is decreased. Neither metallic nor insulator-like behavior is observed at $n_s > 1.3$ 10^{1} cm 2 for any tem perature. However, at slightly lower electron density [Fig. 3 (b)], both components of conductivity are no longer monotonic functions of T:

- (i) at T > 2.5 K (to the left of the rst vertical dotted line), $_{xy}$ < $_{xx}$ < $_{e^2}$ =h and both dim in ish with dim in ishing T which is characteristic for an insulating state. Furtherm ore, according to K hm elnitskii [7], $_{xy}$ in units of $_{e^2}$ =h is a \counter" of the number of bands of extended states below E_F , and because $_{xy}$ $_{e^2}$ =h at T > 2.5 K, there are no extended states below E_F which con rms an insulating state in this temperature region.
- (ii) at 1 $^{<}$ T $^{<}$ 2.5 K (between the two vertical dotted lines), both $_{xx}$ and $_{xy}$ increase with decreasing T, indicating \m etallic" behavior. Both also reach e^2 =2h, the value expected for an extended state ($_{xx}^0$) $_{xy}^0$ = e^2 =2h at = 1=2 and T = 0 [19]).
- (iii) below T = 1 K (to the right of the second dotted line), $_{xx}$ again tends to zero as T = 1 0 while $_{xy}$ approaches = 1 the value of $_{xy}$ now corresponds to one band of extended states below = 1 this is a Q H state.

At even lower n_s [Fig. 3 (c)], both $_{xx}$ (T) and $_{xy}$ (T) change their slope from \insulator-like" to the \m etallic" at T = 1 K but $_{xy}$ always remains < e^2 =2h and the QH conditions are never obtained for this n_s . Finally, for the lowest n_s [Fig. 3 (d)], both (T) decrease monotonically down to the lowest temperatures while $_{xy}$ < $_{xx}$ < e^2 =h; for this n_s , the system always remains insulating. In summary, for n_s > 13 = 10 cm 2 we have observed that the system remains in the QH state regardless of temperature. For n_s = 9.5 = 10 cm 2 , we have observed three dierent types of behavior at = 1: insulator-like at higher temperatures, metallic at intermediate, and QH at T! 0. For lower n_s = 8.6 = 10 cm 2 , we have observed a transition from insulating to metallic types of behavior without a further transition to QH behavior. For even lower n_s = 8.1 = 10 cm 2 , the system remains insulating.

We can understand this elect phenomenologically by examining the position of the energy of the lowest extended state at T = 0. A coording to Refs. [7,8], this is

$$E_{c} = \frac{1}{2}h_{c}^{h} + (c_{c})^{2};$$
 (1)

where $_{\rm c}$ is the cyclotron frequency and $_{\rm c}$ is the relaxation time. Therefore, at constant B ($_{\rm c}$ = const), E $_{\rm c}$ increases with decreasing , i.e., with increasing disorder. Our data show that at $_{\rm c}$ = 1, the elect of temperature is qualitatively similar to the elect of disorder: with decreasing temperature, the energy of the lowest band of extended states decreases. At high T, there are no extended states below the Fermilenergy, and conductivity is due to temperature activation to the nearest extended state. At lower temperatures, the band of extended states crosses the Fermilevel, and we observe a metallic state with characteristic metallic temperature dependencies for both diagonal and Hall conductivities. At still lower temperatures, the band of extended states sinks below the Fermilenergy, $_{\rm xy}$ approaches $_{\rm c}$ =h, and the system enters the QH regime.

Sum m arizing, we have studied the tem perature dependent behavior of the very dilute 2D electron system in silicon at xed lling factor = 1. We have obtained experimental = 1, the energy of the lowest band of extended states decreases relative

to the Ferm i energy as the tem perature is decreased. As a result, this band passes through the Ferm i energy, causing transitions from insulator-like to metal-like and metal to QH-like tem perature dependencies of transport coe cients. The rst of these transitions rejects delocalization with decreasing temperature; this is in sharp contrast to \normal" situation in which lowering the temperature makes a 2DES more localized.

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FIGURES

- FIG.1. (a) D iagonal and Hall resistivity of sample Si-14 in units of h= e^2 vs magnetic eld at three tem peratures and $n_s = 9:1 10^{10}$ cm 2 . The inset schematically shows the expected behavior of extended states in a magnetic eld [7,8]; (b) Inverse $_{xx}$ of sample Si-22 obtained by impedance measurements vs magnetic eld at two temperatures and $n_s = 7:8 10^{10}$ cm 2 . The inset shows a \conventional" $_{xx}$ (B) for higher electron density, $n_s = 1:56 10^{11}$ cm 2 .
- FIG. 2. Tem perature dependence of diagonal resistivity of Si-14 at = 1 for four electron densities. Inset shows activated tem perature dependence of xx at higher tem peratures for the same sample.
- FIG. 3. Tem perature dependence of diagonal and Hall conductivities for sample Si-14 at = 1 for four dierent n_s . Open symbols correspond to xy, closed to xx. Vertical dotted lines approximately separate dierent kinds of tem perature behavior.